



2814

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

7/Election
P. Walker
11-7-01

In re the Application of

Shunichi SEKI et al.

Group Art Unit: 2814

Application No.: 09/423,969

Examiner: Anh D. Mai

Filed: November 17, 1999

Docket No.: 104741

For: THIN FILM PATTERNING SUBSTRATE AND SURFACE TREATMENT
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TECHNOLOGY CENTER 2800RESPONSE TO RESTRICTION REQUIREMENTDirector of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the Restriction Requirement mailed October 2, 2001, Applicants provisionally elect Group I, claims 1-29, 48, 69-71, 73 and 75-79, drawn to a semiconductor device, classified in class 257, subclass 79⁺, with traverse.

It is also respectfully submitted that the subject matter of all claims 1-80 is sufficiently related that a thorough search for the subject matter of any one group of claims would encompass a search for the subject matter of the remaining claims. Thus, it is respectfully submitted that the search and examination of the entire application could be made without serious burden. See MPEP §803 in which it is stated that "if the search and examination of the entire application can be made without serious burden, the Examiner must examine it on the merits even though it includes claims to distinct or independent inventions" (emphasis added). It is respectfully submitted that this policy should apply in the present application in order to avoid unnecessary delay and expense to Applicants and duplicative examination by the Patent Office.

Thus, withdrawal of the Restriction Requirement is respectfully requested.

Respectfully submitted,



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Date: November 1, 2001

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